

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :

HARADA et al.

Group Art Unit: TBA

Serial No.: TBA

Examiner: TBA

Filed: Herewith

For: POLYMERS, RESIST COMPOSITIONS AND PATTERNING PROCESS

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

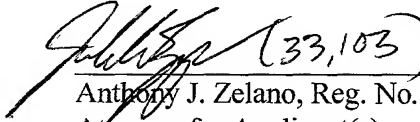
5. (Amended) A chemically amplified, positive resist composition comprising
 - (A) the polymer of claim 1
 - (B) an organic solvent, and
 - (C) a photoacid generator.

REMARKS

The claims have been amended to remove the multiple dependency therein.

The Commissioner is hereby authorized to charge any fees associated with this response or credit any overpayment to Deposit Account No. 13-3402.

Respectfully submitted,


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Attorney for Applicant(s)

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Attorney Docket No.: KOJIM-449

Date: February 28, 2002

VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE CLAIMS:

Please amend the claims as follows:

5. (Amended) A chemically amplified, positive resist composition comprising
- (D) the polymer of [any one of claims 1 to 3] claim 1
 - (E) an organic solvent, and
 - (F) a photoacid generator.